

*cont*

33. (New) A local clean equipment having installed therein a chemical filter for trapping at least one of organic substances and inorganic substances and also having installed therein an air filter for trapping suspended particulate substances in the air, said air filter being installed downstream of said chemical filter, characterized in that; an air filter according to Claim 26 is installed as said air filter.

34. (New) A local clean equipment having installed therein a chemical filter for trapping at least one of organic substances and inorganic substances and also having installed therein an air filter for trapping suspended particulate substances in the air, said air filter being installed downstream of said chemical filter, characterized in that; an air filter according to Claim 28 is installed as said air filter.

*Silf 65*

35. (New) A method for manufacturing semiconductors, wherein a silicon wafer for said semiconductor is processed in at least one of a clean room and a local facility having an air filter as defined in Claim 27.

*Silf 67*

36. (New) A method for manufacturing semiconductors, wherein a silicon wafer for said semiconductor is processed in at least one of a clean room and a local facility having an air filter as defined in Claim 28.

*Silf 67*

37. (New) A semiconductor device made by processing a silicon wafer in at least one of a clean room and a local facility having an air filter as defined in Claim 27.

*Silf 67*

38. (New) A semiconductor device made by processing a silicon wafer in at least one of a clean room and a local facility having an air filter as defined in Claim 28.